

INTERFERENCE
EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L32	0	((mask\$3 near4 inspect\$4) and opc and layer and relation\$6 and feature and lithography and wafer and allocat\$3 and beam and power).CLM.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/22 06:21

EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	311	(mask near6 writ\$4) and opc and layer and ("716"/\$.ccls. or "430"/\$.ccls.)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/22 05:51
L2	46	(mask near6 writ\$4) and (multiple same layer) and print and opc and ("716"/\$.ccls. or "430"/\$.ccls.)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/22 05:51
L3	47	(mask near5 lithography) and (design same data) and (multiple same layer) and opc and writ\$3 and ("716"/\$.ccls. or "430"/\$.ccls.)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/22 05:51
L4	17	(mask near5 lithography) and (design same data) and tag and opc and ("716"/\$.ccls. or "430"/\$.ccls.)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/22 05:51
L5	21	(mask same lithograph\$3) and (design same data) and tag and opc and ("716"/\$.ccls. or "430"/\$.ccls.)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/22 05:51
L6	20	(mask same lithography) and (design same data) and tag and opc and ("716"/\$.ccls. or "430"/\$.ccls.)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/22 05:51
L7	17	(mask near5 lithography) and (design same data) and tag and opc and ("716"/\$.ccls. or "430"/\$.ccls.)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/22 05:51
L8	97	(mask near5 lithography) and (design same data) and (multiple same layer) and opc and ("716"/\$.ccls. or "430"/\$.ccls.)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/22 05:51

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L9	72	(mask same writ\$4) and (design same data) and (multiple same layer) and opc and ("716"/\$.ccls. or "430"/\$.ccls.)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/22 05:51
L10	63	(mask same writ\$4) and (design same data) and (multiple same layer) and print\$4 and opc and ("716"/\$.ccls. or "430"/\$.ccls.)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/22 05:51
L11	74	(mask near6 writ\$4) and (multiple same layer) and print\$4 and opc and ("716"/\$.ccls. or "430"/\$.ccls.)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/22 05:51
L12	39	(mask same writ\$4) and (design same data) and (multiple same layer) and print and opc and ("716"/\$.ccls. or "430"/\$.ccls.)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/22 05:51
L13	101	(mask same writ\$4) and (design same data) and layer and opc and feature and context	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/22 05:51
L14	187	(mask near6 writ\$4) and opc and print and ("716"/\$.ccls. or "430"/\$.ccls.)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/22 05:51
L15	217	(mask same writ\$4) and opc and print and ("716"/\$.ccls. or "430"/\$.ccls.)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/22 05:51
L16	404	(mask same writ\$4) and opc and ("716"/\$.ccls. or "430"/\$.ccls.)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/22 05:51

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L17	234	(mask same writ\$4) and (design same data) and layer and opc and ("716"/\$.ccls. or "430"/\$.ccls.)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/22 05:51
L18	46	(mask near6 writ\$4) and (multiple same layer) and print and writ\$3 and opc and ("716"/\$.ccls. or "430"/\$.ccls.)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/22 05:51
L19	260	(mask near4 inspect\$4) and opc and layer and ("716"/\$.ccls. or "430"/\$.ccls.)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/22 05:51
L20	4878	mask near4 inspect\$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/22 05:51
L21	175	(mask near6 writ\$4) and opc and print and layer and ("716"/\$.ccls. or "430"/\$.ccls.)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/22 05:51
L22	117	(mask near4 inspect\$4) and opc and layer and relation\$6 and ("716"/\$.ccls. or "430"/\$.ccls.)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/22 05:51
L23	1374	(mask near6 writ\$4) and ("716"/\$.ccls. or "430"/\$.ccls.)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/22 05:51
L24	92	(mask near4 inspect\$4) and opc and layer and relation\$6 and feature and lithography and wafer and ("716"/\$.ccls. or "430"/\$.ccls.)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/22 06:18

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L25	301	(mask same writ\$4) and (design same data) and layer and opc	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/22 05:51
L26	5092	(mask same writ\$4) and (design same data)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/22 05:51
L27	404	(mask near4 inspect\$4) and opc	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/22 05:51
L28	344	(mask near4 inspect\$4) and opc and layer	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/22 05:51
L29	7	(mask\$3 near4 inspect\$4) and opc and layer and relation\$6 and feature and lithography and wafer and allocat\$3	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/22 06:19
L30	4	(mask\$3 near4 inspect\$4) and opc and layer and relation\$6 and feature and lithography and wafer and allocat\$3 and beam	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/22 06:19
L31	4	(mask\$3 near4 inspect\$4) and opc and layer and relation\$6 and feature and lithography and wafer and allocat\$3 and beam and power	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/22 06:21
L32	0	((mask\$3 near4 inspect\$4) and opc and layer and relation\$6 and feature and lithography and wafer and allocat\$3 and beam and power).CLM.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/22 06:21

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